

Case Docket No. ASMEX.333A Date: April 9, 2002

Page 1

In re application of:

Todd, et al.

App. No.

10/074,564

Filed

February 11, 2002

For

THIN FILMS AND

METHODS OF MAKING

THEM (as amended)

Examiner

Unknown

Art Unit

Unknown

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2327, Arlington, VA 22202, on

## UNITED STATES PATENT AND TRADEMARK OFFICE

P.O. Box 2327

Arlington, VA 22202

Sir:

Transmitted herewith is a Preliminary Amendment in the above-identified application.

The fee has been calculated as shown below:

		CL	AIMS AS FI	LED			•		
	CLAIMS REMAINING AFTER AMENDMENT		HIGHEST NO PREVIOUSLY PAID FOR	•	PRESENT EXTRA		RATE	A	ADDITIONAL FEE
Total Claims	54	_	54	=	0	×	\$18	=	\$0
Independent Claims	4	_	4	=	0	×	\$84	=	\$0
If application has been amended to contain multiple dependent claim(s), then add \$130 =									
Time Extension Fee					. ,				\$0
	TOTAL AD	DITIONA	L FEE FOR	THIS	SAMEND	ME	NT		\$0

(X) Return prepaid postcard.

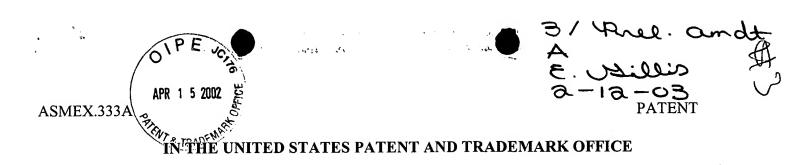
(X) Please charge any additional fees, including any fees for additional extension of time, or credit overpayment to Deposit Account No. 11-1410.

Joseph J. Mallon

Registration No. 39,287

Attorney of Record

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Applicant	:	Todd, et al.	) Group Art Unit Unknown
Appl. No.	:	10/074,564	I hereby certify that this correspondence and all marked attachments are being deposited with the United States Postal Service as first-
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For	:	THIN FILMS AND METHODS OF MAKING THEM (as amended)	) 4/9/02 (Date)
Examiner	:	Unknown	Joseph J. Mallon, Reg. No. 39,287

## PRELIMINARY AMENDMENT

United States Patent and Trademark Office P.O. Box 2327 Arlington, VA 22202

Dear Sir:

Prior to examination, please amend the above-referenced application as follows:

## IN THE TITLE:

Please amend the title to read as follows:

THIN FILMS AND METHOD OF MAKING THEM

## <u>IN THE ABSTRACT</u>:

Please replace the Abstract of the Disclosure with the following new Abstract:

Thin, smooth silicon-containing films are prepared by deposition methods that utilize a silicon-containing precursor. In preferred embodiments, the methods result in Si-containing films that are continuous and have a thickness of about 150 Å or less, a surface roughness of about 5 Å rms or less, and a thickness non-uniformity of about 20% or less. Preferred silicon-containing films display a high degree of compositional uniformity when doped or alloyed with other elements. Preferred deposition methods provide improved manufacturing efficiency and